

0160-0193-0 PCT



#81B  
10/3/01

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :  
HIROSHI IKEDA ET AL : EXAMINER: VANOY, T.  
SERIAL NO: 09/463,961 :  
FILED: MAY 25, 2000 : GROUP ART UNIT: 1754  
FOR: METHOD AND APPARATUS  
FOR PROCESSING EXHAUST  
GAS OF SEMICONDUCTOR  
FABRICATION

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

RECEIVED  
OCT 03 2001  
TC 1700

SIR:

In response to the Office Action dated June 19, 2001, the period for response having been extended to October 19, 2001, by a petition for extension of time filed herewith, please amend the application identified above as follows (marked-up copy of amendments attached):

IN THE TITLE

Please replace the title with the following title:

--PROCESS AND APPARATUS FOR TREATING SEMICONDUCTOR  
PRODUCTION EXHAUST GASES--.

IN THE SPECIFICATION

Page 1, after the title, please insert the continuing data:

This application is a 371 of PCT/JP98/04666 filed October 15, 1998.

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